

15-1-2013

EE 5390

Note Title

15-01-2013

Analog IC Design

class hrs — 13 slot

M — 9 — 9:50 am

Tu — 8 — 8:50 am

W — 12 — 12:50 pm

F — 11 — 11:50 am

Th — 4:45 — 5:35 pm

Textbook : Design of Analog CMOS
Integrated Circuits

— Behzad Razavi

Tata McGrawHill © 2002

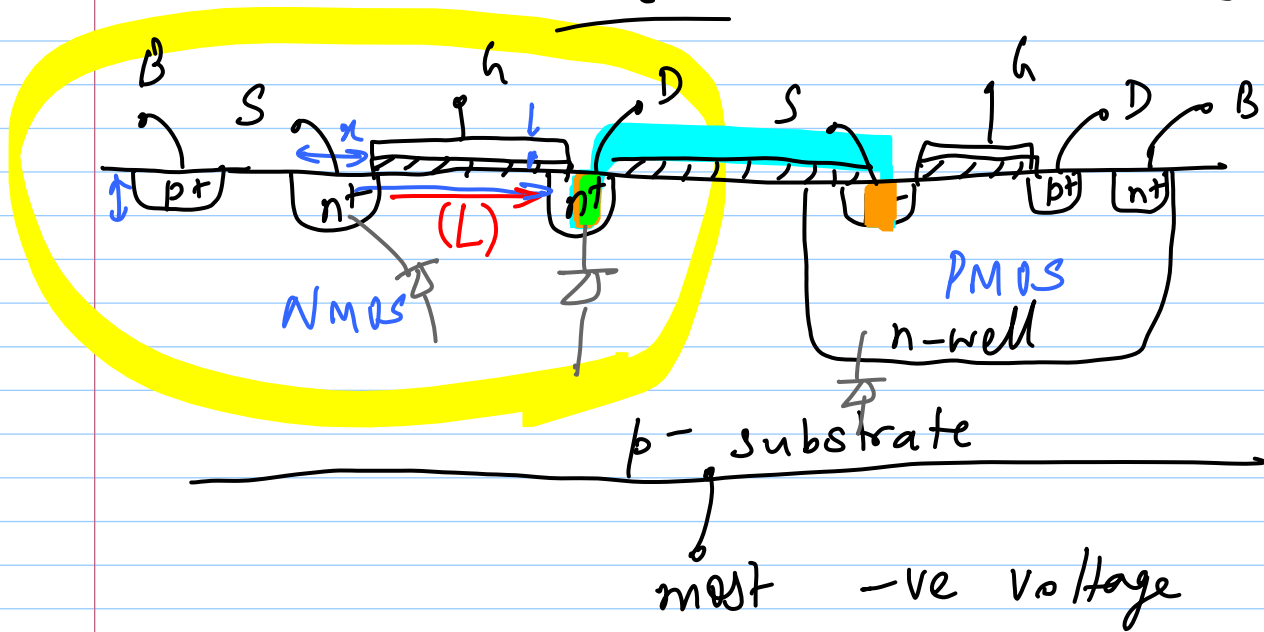
Pre-req : EC 3102 / EC 5135

Grading : HW, Assign., Projects — 30%.

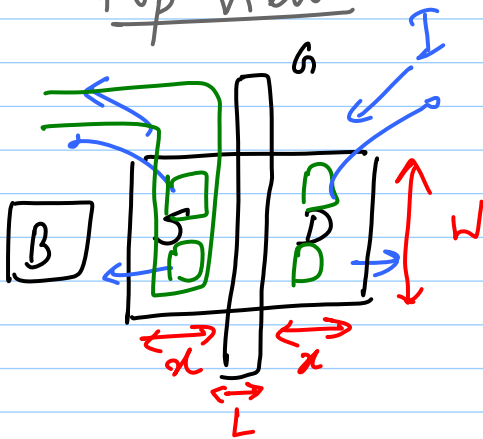
Quiz 1 & 2 — 15% each

Final exam — 40%.

Lec 1 - CMOS ICs



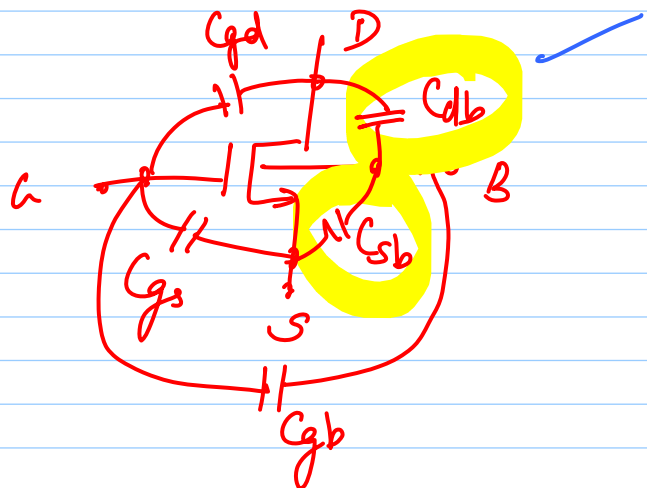
top view



$$\left(\frac{W}{L}\right), V_T, C_{ox}, \lambda, \mu_n, \mu_p \dots$$

$a \uparrow \Rightarrow C_{db}, C_{sb} \uparrow$

$a \leftrightarrow$ power handling capability



Layers

- * Substrate (p^-)
- * n-well (n)
- * diffusions (n^+ , p^+)
- * oxide (SiO_2)
- * polysilicon (n)
- * metal (Cu , Al)
- * contact & vias

Resistors

n-well, poly, n^+ , p^+ , metal

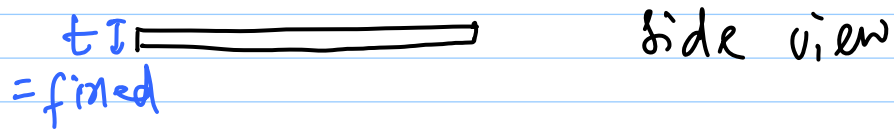
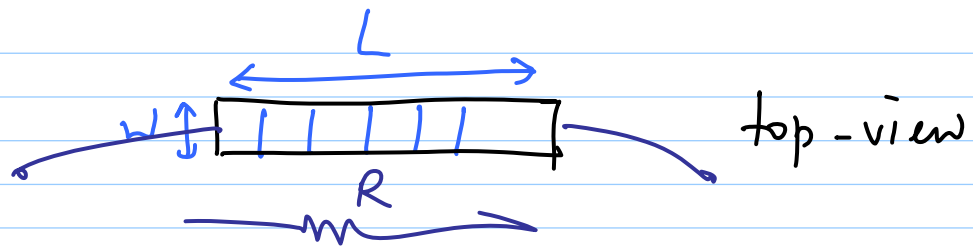
$k\Omega$ to $10^5 \Omega$ per $\square$
 ~~lightly doped~~
 ~~high ρ~~
 (t)

$10^3 \Omega$ per $\square$
 $10^1 \Omega$ to $100^5 \Omega$

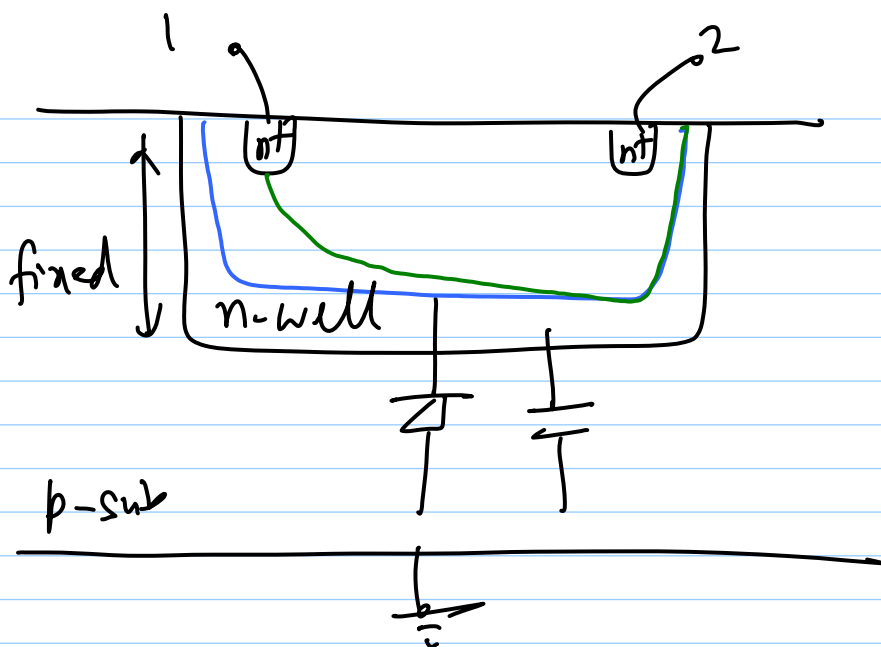
$m\Omega$ to Ω per $\square$

choose R based on

- * tolerance
- * area
- * freq. characteristics (parasitics)
- * linearity
- * temp. co.



$$R = \frac{\rho \cdot L}{t \cdot w} = \underbrace{R_{sh}}_{\substack{\text{sheet resistance} \\ \Omega/\square}} \cdot \frac{L}{w}$$



$$I = \frac{V}{R} + \alpha_2 V^2 + \alpha_3 V^3 + \dots$$

